ABSTRACT OF THE DISCLOSURE

PROJECTION EXPOSURE APPARATUS AND EXPOSURE METHOD

In the projection exposure apparatus of the present invention, alignment controller Q33 selects, from baseline memory Q34, the appropriate baseline amount in correspondence with the insertion, into optical axes Q1X and QX in positional detection optical system Q, of illumination light limiting member q1 and phase plate q2. In this way, by using a baseline amount corresponding to a modification of the optical conditions, a desired position on substrate W is accurately disposed beneath the projection optical system P. Furthermore, even when there are changes in the electrical circuit characteristics of the positional detection optical system Q as a result of changes in the amplification ratio of the amplifier Q31, the alignment controller Q33 conducts processing which is identical to that described above. By means of this, even when the characteristics of the positional detection optical system are changed, the baseline amount corresponding to the changes in characteristics is corrected, and reliable alignment is possible.